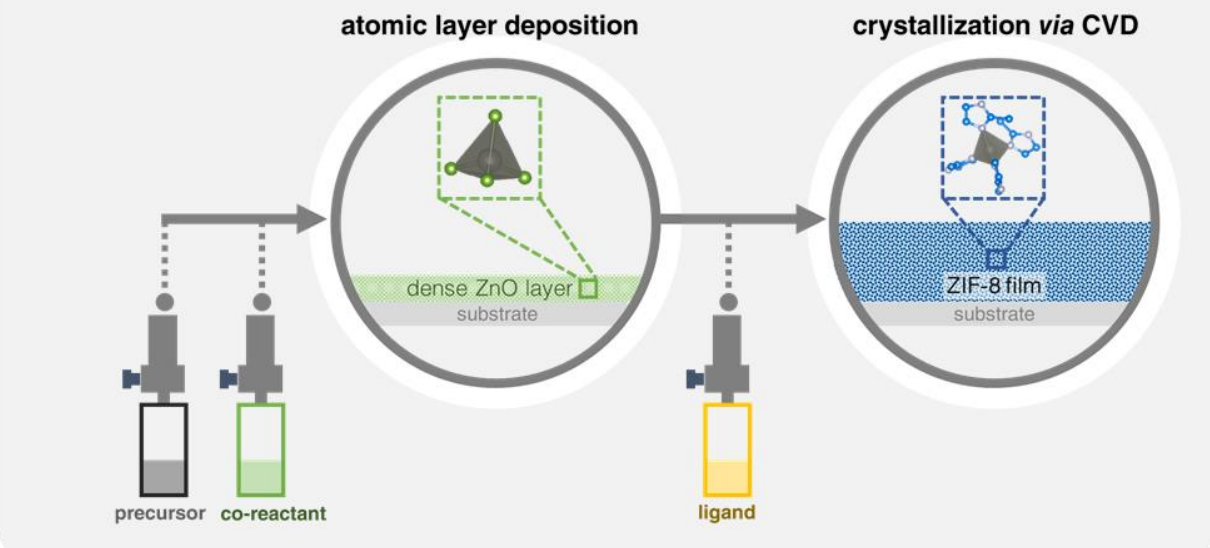
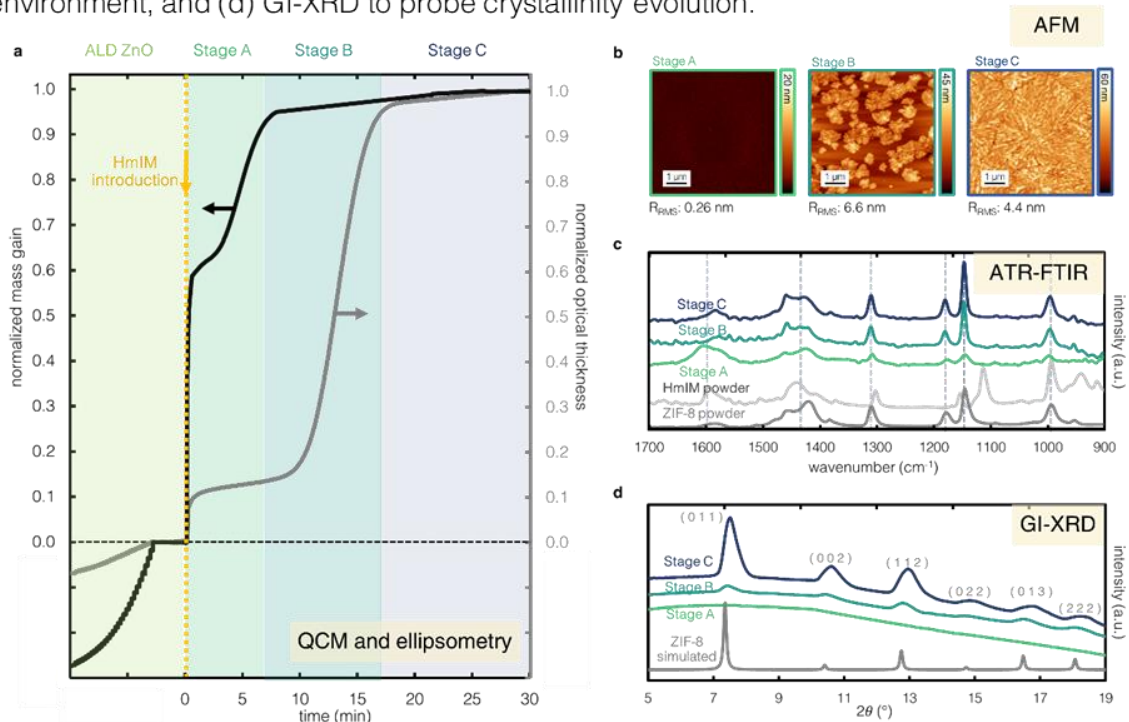


Schematic of the MOF-CVD process

(1) ALD ZnO followed by (2) conversion to ZIF-8 *via* CVD



In situ characterization | (a) QCM and ellipsometry exhibiting real-time gravimetric and spectroscopic metrology, (b) AFM topography images, (c) ATR-FTIR showing chemical environment, and (d) GI-XRD to probe crystallinity evolution.



Large scale demonstration to full 200 mm device-grade Si wafers showcasing uniform thickness for a 100-point radial mapping via ellipsometry

